Artificial Pit Its Reaction to BCP and EP and Its Removal by E-beam Re-melting

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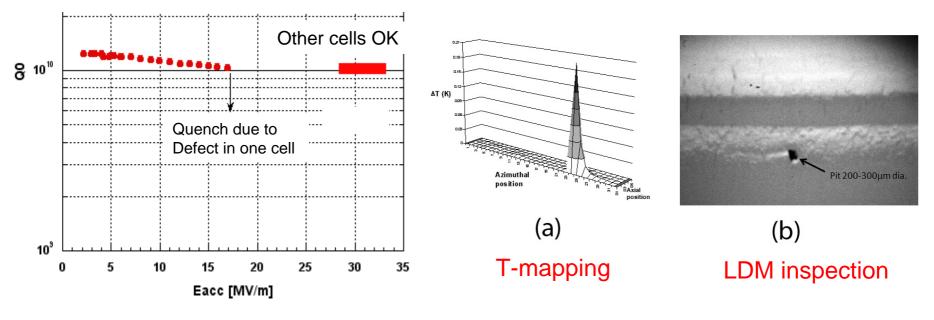
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Pit and Its Relevance to Quench



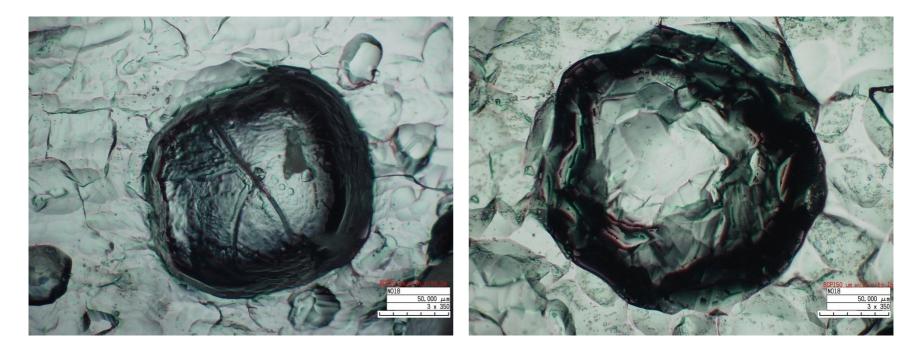
- A pit (200-300 μm in dia. ~ 50 μm in depth) correlated $\,$ to quench at 17 MV/m in A15.
- One pit limits whole cavity as other cells 28-33 MV/m.
- Pit/bump (sub-mm sized) correlated to quench <20 MV/m in AES1 by FNAL/KEK/Kyoto collaboration [Champion et al., ASC08]
- Another fact: AES1 quench limit insensitive to repeated EP, same responsible cell pair.





BCP Effect on Pit

A pit becomes a bigger pit after more BCP



BCP 20 µm

BCP 150 µm

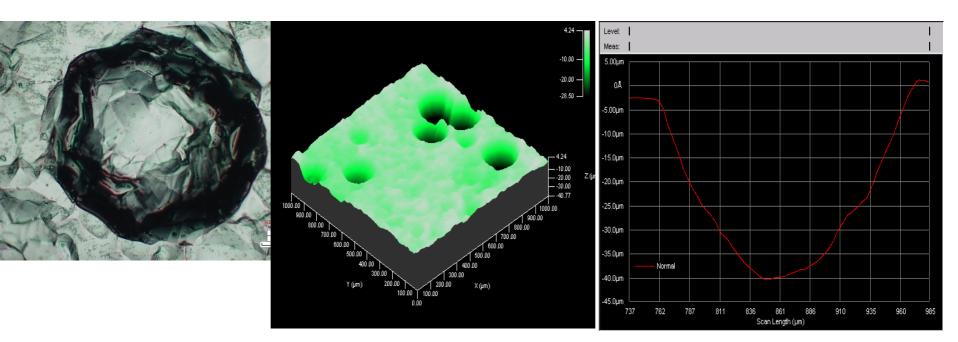


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BCP Effect on Pit

After BCP 150 μm



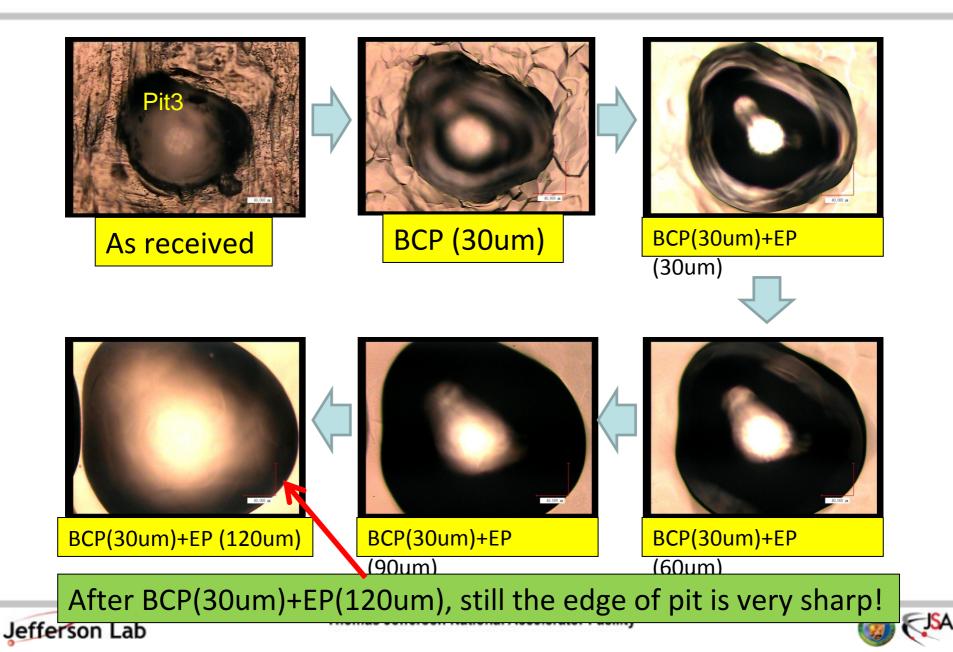
Slope angle 26°-47°



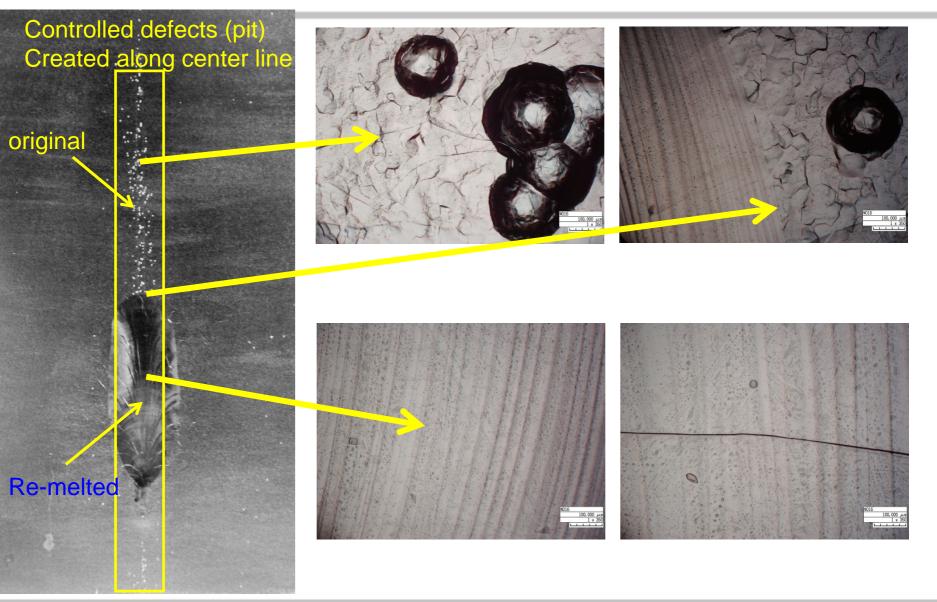
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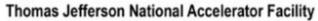


EP Effect on Pit (KEK)



E-beam Re-melting Removes Pit





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Conclusion

 Preliminary experiments show a pit can not be removed by BCP or EP, even after heavy (~150μm) removal.

• This is true for pits of various sizes (sub-mm in diameter, up to 200 μm in depth).

• Preliminary profiling of pits show geometric features that could cause local magnetic field enhancement of ~ X2.

• Preliminary experiments show encouraging results of removing localized pits by using the E-beam re-melting method.

• Further studies under way to characterize relationship between pit features and quench behavior.



